

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Serial No.: 10/797,876
Applicant: Anthony Dip et al.
Art Unit: 2811
**Title: SILICON GERMANIUM SURFACE LAYER FOR HIGH-K
DIELECTRIC INTEGRATION**
Attorney Docket: TPS-007
Confirmation No.: 5070

Cincinnati, Ohio 45202

June 9, 2006

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

RESPONSE TO ELECTION/RESTRICTION REQUIREMENT

This paper is responsive to the Office Action mailed May 31, 2006. The Examiner has indicated that claims 1-8, 10, 11 and 13-21 are pending in the application and are subject to restriction and/or election requirement. Specifically, we understand that the Examiner has grouped the claims between Group I, claims 1-8, 10-11 and 13-20, and Group II, claim 21. Group I is directed to a method of forming a semiconductor device, and Group II is directed to a transistor device. Applicants hereby elect Group I, claims 1-8, 10-11 and 13-20, directed to a method.

Examination on the merits of elected claims 1-8, 10-11 and 13-20 is respectfully requested.

Application Serial No. 10/797,876
Response dated June 9, 2006
Reply to Office Action of May 31, 2006

Respectfully submitted,

WOOD, HERRON & EVANS LLP.

By: /Kristi L. Davidson/
Kristi L. Davidson, Reg. No. 44,643

2700 Carew Tower
441 Vine Street
Cincinnati, OH 45202
513/241-2324 (voice)
513/241-6234 (facsimile)
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